



(11) **EP 2 206 746 A8**

(12) **CORRECTED EUROPEAN PATENT APPLICATION**
published in accordance with Art. 153(4) EPC

(15) Correction information:
Corrected version no 1 (W1 A1)
Corrections, see
Bibliography INID code(s) 71

(51) Int Cl.:
C08L 83/16 ^(2006.01) **C08G 77/62** ^(2006.01)
C08K 5/17 ^(2006.01) **C09D 7/12** ^(2006.01)
C09D 183/16 ^(2006.01) **H01L 21/312** ^(2006.01)

(48) Corrigendum issued on:
18.08.2010 Bulletin 2010/33

(86) International application number:
PCT/JP2008/069406

(43) Date of publication:
14.07.2010 Bulletin 2010/28

(87) International publication number:
WO 2009/054522 (30.04.2009 Gazette 2009/18)

(21) Application number: **08840790.3**

(22) Date of filing: **27.10.2008**

(84) Designated Contracting States:
AT BE BG CH CY CZ DE DK EE ES FI FR GB GR
HR HU IE IS IT LI LT LU LV MC MT NL NO PL PT
RO SE SI SK TR

(30) Priority: **26.10.2007 JP 2007279374**

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(54) **COMPOSITION CONTAINING POLYSILAZANE COMPOUND, WHICH CAN PROVIDE DENSE SILICEOUS FILM**

(57) The present invention provides a polysilazane-containing composition capable of forming a dense siliceous film more rapidly and at a lower temperature than known polysilazane-containing composition. In a process for forming the siliceous film, the composition comprising a polysilazane compound, a particular amine compound and a solvent is coated on a substrate and

converted into a siliceous substance. The particular amine compound preferably contains two amine groups separated from each other at the distance corresponding to five C-C bonds or more, and the amine groups preferably have hydrocarbon substituent groups.

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